

58TH DEVICE RESEARCH CONFERENCE

PRELIMINARY ADVANCE PROGRAM

Monday AM, June 19, 2000

DRC Plenary Session (Sturm Auditorium)

9:30 AM - 12:05 PM

Session Chair: Mark Rodder

Session Organizer: Mark Rodwell

Plenary Speakers:

9:30 AM, I.1 Invited

Silicon MOSFETs (Conventional and Non-Traditional) at the Scaling Limit: *James D. Plummer*¹; ¹Stanford University, Department of Electrical Engineering

10:10 AM Break

10:35 AM, I.2 Invited

Silicon Micromachines for Science and Technology: *David Bishop*¹; ¹Bell Laboratories/Lucent Technologies, Murray Hill, NJ 07974 USA

11:15 AM, I.3 Invited

The Future of Organic Semiconductor Devices: *Ananth Dodabalapur*¹; ¹Bell Laboratories, Lucent Technologies Murray Hill, NJ 07974 USA

Monday PM, June 19th, 2000

Session II.A. (DUC Ballroom A/B)
Silicon-Based FETs

Session Organizer: Edward Nowak, IBM

2:00 PM, II.A.-1, Invited

Device Characteristics of Crystalline Epitaxial Oxides on Silicon: *V. Kaushik*¹; *K. Eisenbeiser*¹; *B-Y. Nguyen*¹; *J. Finder*¹; *Z. Yu*¹; *J. Ramadani*¹; *R. Droopad*¹; *J. Curlless*¹; *C. Overgaard*¹; *L. Prabhu*¹; *J. Conner*¹; Motorola Digital/DNA Laboratories, Mats. & Struct. Lab., 3501 Ed Bluestein Blvd., MD K20, Austin, TX 78721 USA

2:30 PM, II.A.-2

SiGe and Si PMOSFET's Characteristics with ZrO₂ Gate Dielectric: *T. Ngai*¹; W. J. Qi¹; X. Chen¹; R. Sharma¹; J. L. Fretwell¹; J. C. Lee¹; S. K. Banerjee¹; ¹The University of Texas at Austin, Mail Code R9950, Microelect. Res. Ctr., R9950, Austin, TX 78758 USA

2:50 PM, II.A.-3

30nm Ultra-Thin Body SOI MOSFET with Selectively Deposited Ge Raised S/D: *Yang-Kyu Choi*¹; Chenming Hu¹; ¹University of California-Berkeley, 211-41 Cory Hall #1772, Berkeley, CA 94720-1772 USA

3:10 PM, II.A.-4

Vertical P-MOSFETS with Heterojunction Between Source/Drain and Channel: *Xiangdong Chen*¹; Qiqing Ouyang¹; Kou-Chen Liu¹; Zhonghai Shi¹; Al Tasch¹; Sanjay Banerjee¹; Xiangdong Chen¹; ¹University of Texas at Austin, Microelect. Res. Ctr., 10100 Burnet Rd., Bldg. 160, Rm. 204F, Austin, TX 78758 USA

3:30 PM Break

3:50 PM, II.A.-5

Bandgap Engineering in Deep Submicron Vertical pMOSFETs: *Q. Quyang*¹; X. D. Chen¹; S. Mudanai¹; D. L. Kencke¹; A. F. Tasch¹; S. K. Banerjee¹; ¹The University of Texas at Austin, R9950, Microelect. Res. Ctr., 2.608B, Austin, TX USA

4:10 PM, II.A.-6

High Room Temperature Hole Mobility in Ge_{0.7}Si_{0.3}/Ge/Ge_{0.7}Si_{0.3} Modulation Doped Heterostructures in the Absence of Parallel Conduction: *S. Madhavi*¹; V. Venkataraman¹; Y. H. Xie²; ¹Indian Institute of Science, Dept. of Phys., Bangalore-560 012 India; ²UCLA

4:30 PM, II.A.-7

Low-Noise SiGe pMODFETs on Sapphire with 116 GHz, f_{max}: *S. J. Koester*¹; R. Hammond¹; J. O. Chu¹; P. M. Mooney¹; J. A. Ott²; C. S. Webster²; I. Lagnado³; P. R. de la Houssaye³; ¹IBM Corporation, Thomas J. Watson Research Center, P.O. Box 218, Yorktown Heights, NY 10598 USA; ²IBM Microelectronics; ³Space and Naval Warfare Systems Center, CA

Monday PM, June 19, 2000

Session II.B. (DUC Ballroom C/D)
GaN-FETs

Session Organizer: Ilesanmi Adesida, University of Illinois

2:00 PM, II.B.-1 Invited

AlGaN/GaN HEMTs and HBTs for Microwave Power: *Umesh K. Mishra*¹; R. Vetry¹; L. M. McCarthy¹; Y. Smorchkova¹; S. Keller¹; H. Xing¹; N. Zhang¹; J. S. Speck¹; R. York¹; S. Denbaars¹; ¹University of California, Elect. & Comp. Eng. and Mats., Depts., Santa Barbara, CA 93106 USA

2:30 PM, II.B.-2

High Power Demonstration at 10 GHz with GaN/AlGaIn HEMT Hybrid Amplifiers: *S. T. Sheppard*¹; W. L. Pribble¹; D. T. Emerson¹; Z. Ring¹; R. P. Smith¹; S. T. Allen¹; J. W. Palmour¹; ¹Cree, Inc., 4600 Silicon Dr., Durham, NC 27703 USA

2:50 PM, II.B.-3

Wideband Al/GaN/GaN HEMTs on SiC for Low Noise Applications: *Wu Lu*¹; J. W. Yang¹; M. Asif Khan¹; I. Adesida¹; ¹University of Illinois at Urbana-Champaign, Microelect. Lab. & Dept. of Elect. & Comp. Eng., Urbana, IL 61801 USA

3:10 PM, II.B.-4

Recessed-Gate GaN NESFET using ICP-RIE for High Temperature Microwave Applications: *C. Lee*¹; W. Lu¹; E. Piner¹; I. Adesida¹; ¹University of Illinois, Dept. of Elect. and Comp. Eng. and Microelect. Lab., 208 N. Wright St., Urbana-Champaign, IL 61801 USA

3:30 PM Break

3:50 PM, II.B.-5

GaN-based MESFETs and DC-MOSFETs: *R. Gaska*¹; M. A. Khan²; X. Hu²; L. Simin²; J. Yang²; J. Deng³; S. Rumyantsev³; M. S. Shur³; ¹Sensor Electronic Technology, Inc., 21 Cavalier Way, Latham, NY 12110 USA; ²University of South Carolina, SC USA; ³RPI

Monday PM, June 19, 2000, 5:30 PM - 8:00 PM

**Session III. (DUC Gallery)
Poster Session**

III.-1

New Device Models of Quantum Well Infrared Photodetectors: Janet L. Pan¹; ¹Yale University, Becton Center, Rm. 505, 15 Prospect St., New Haven, CT 06520-8284 USA

III.-2

SiGe Low Loss Waveguides for 1.3 um Grown by Selective Epitaxy: A. Vonsovici¹; L. Vescan¹; S. P. Pogossian¹; ¹University of Surrey, Guildford GU2 XH UK

III.-3

Ferromagnetic Fe/Ag-GaAs Waveguide Structures for Wideband Microwave Integrated Notch Filter Devices: Wei Wu¹; C. S. Tsai¹; C. C. Lee¹; H. J. Yoo¹; H. Hopster¹; D. L. Mills¹; ¹University of California, Dept. of Elect. and Comp. Eng. and Instit. of Surf. and Interf. Sci., Irvine, CA 92697 USA

III.-4

Memory Devices Utilizing Resonant Tunneling in Nanocrystalline Silicon Superlattices: L. Tsybeskov¹; L. Montes¹; A. Aron¹; R. Krishnan¹; P. Fauchet¹; B. White²; ¹University of Rochester, Dept. of Electr. & Comp. Eng., Computer Studies Bldg. 511, 160 Trustee Rd., Rochester, NY 14627-0231 USA; ²Motorola, SPS, Austin, TX USA

III.-5

Vacuum Microelectronic Electron Emitter by InP Double Barrier Diode Toward RF Application: Y. Miyamoto¹; M. Kurita¹; K. Furuya¹; ¹Tokyo Institute of Technology, Dept. of Elect. & Electronic Eng., 2-12-1, O-okayama, Meguro, Tokyo 152-8552 Japan

III.-6

SB-Heterostructure Millimeter-Wave Zero-Bias Diodes: J. N. Schulman¹; D. H. Chow¹; C. W. Pobanz¹; H. L. Dunlap¹; C. D. Haeussler¹; ¹HRL Laboratories, LLC, 3011 Malibu Canyon Rd., Malibu, CA 90265 USA

III.-7

Five-Terminal Amorphous Silicon Thin-Film Transistor Structure: Sandrine Martin¹; Y. Feillens¹; J. Kanicki¹; ¹University of Michigan, Dept. of Elect. Eng. and Comp. Sci., 216 Engineering Programs, Bldg. 2609 Draper, Ann Arbor, MI 48109-2101 USA

III.-8

Lifetime Control By Low Energy Electron Irradiation and Hydrogen Annealing: J. Joe¹; J. Park¹; H. J. Kim¹; S. H. Lee¹; Z. Y. Shen¹; Y. Nishihara¹; ¹Ajou University, Dept. of Elect. Eng., Suwon 442-749 Korea

III.-9

Modeling High K Gate Current from p-type Si Inversion Layers: Y. Y. Fan¹; S. Mudanai¹; W. Qi¹; J. C. Lee¹; A. F. Tasch¹; L. F. Register¹; S. K. Banerjee¹; ¹The University of Texas at Austin; Microelect. Res. Ctr., 2.608A, R9950, Austin, TX 78758 USA

III.-10

Scaling Limit of Silicon Nitride Gate Dielectric for Future CMOS Technologies: Y. C. Yeol¹; Q. Lu¹; W. Lee¹; T. King¹; C. Hu¹; ¹University of California, Dept. of Elect. Eng. and Comp. Sci., Berkeley, CA 94720 USA

III-11

60nm Planarized Ultra-thin Body Solid Phase Epitaxy MOSFETs: Peiqui Xuan¹; J. Kedzierski¹; V. Subramanian¹; J. Bokor¹; T. King¹; C. Hu¹; ¹University of California, Dept. of Elect. Eng. and Comp. Scis., Berkeley, CA 94720 USA

III.-12

Design Optimization of Stacked Gate Oxides with Easy Evaluation of Gate Leakage in Deep Submicron MOSFET: Jinlong Zhang¹; Jiann S. Yuan¹; Yi Ma¹; Anthony S. Oates¹; ¹University of Central Florida, Schl. of Elect. Eng. and Comp. Sci., Orlando, FL 32816 USA

III.-13

A Novel Sub-10nm Transistor: Pranav Kalavade¹; K. C. Saraswat¹; ¹Stanford University, 725 Reseda Dr., 32 Sunnyvale, CA 94087 USA

III.-14

Reliability and Modeling of GaN-Based Light Emitting Diode: Hyunsoo Kim¹; Ji-Myon Lee¹; B. Huh¹; Sang-Woo Kim¹; Dong-Joon Kim¹; Seong-Ju Park¹; Hyunsang Hwang¹; ¹Kwangju Institute of Science and Technology, Dept. of Mats. Sci. and Eng., #1, Oryong-dong, Puk-gu, Kwangju 500-712 Korea

III.-15

pH Sensors Based on Wide Bandgap Semiconductors: A. Denisenko¹; A. Aleksov¹; I. Daumiller¹; E. Kohn¹; ¹University of Ulm, Dept. of Elect. Devs. & Cir., Albert-Einstein-Allee 45, 89081 Ulm, Germany

III.-16

Very Short Channel Metal-Gate Schottky Source/Drain SOI-PMOSFETs and their Short Channel Effect: A. Itoh¹; M. Saitoh¹; M. Asada¹; ¹Tokyo Institute of Technology, Fac. of Eng., Dept. of Elect. and Elect. Eng., 2-12-1 O-okayama, Meguro-ku, Tokyo 152 8552 Japan

III.-17

Electron Transport in a Single Silicon Quantum Dot Structure using A Vertical Silicon Probe: Katsuhiko Nishiguchi¹; Shunri Oda¹; ¹Tokyo Institute of Technology, Res. Ctr. for Quantum Effect Electr., O-okayama, Meguro-Ku, Tokyo 152-8552, Japan

III.-18

A Silicon MOSFET/Field Emitter Array Fabricated using CMP: C. Y. Hong¹; A. I. Akinwande¹; ¹Massachusetts Institute of Technology, Microsystems Technology Laboratories, 39-653, 60 Vassar St. Cambridge, MA 02139 USA

III.-19

0.13 um Gate-Length In_{0.52}A_{10.48}As/In_{0.53}Ga_{0.47}As Metamorphic HEMTs on GaAs Substrate: D. C. Dumka¹; G. Cueva¹; W. E. Hoke²; P. J. Lemonias²; I. Adesida¹; ¹University of Illinois, Dept. of Elect. and Comp. Eng. and Microelec. Lab., 208 N. Wright St., Urbana-Champaign, IL 61801 USA; ²Raytheon RF Components, MA USA

III.-20

HBT on LEO GaN: L. McCarthy¹; Y. Smorchkova¹; P. Fini¹; H. Xing¹; M. Rodwell¹; J. Speck¹; S. DenBaars¹; U. Mishra¹; ¹University of California-Santa Barbara, ECE Dept., Santa Barbara, CA 93106 USA

Tuesday AM, June 20, 2000

Session IV. (*DUC Ballroom*) Emerging Technologies

Session Organizer: Mark Rodwell

Session Co-Chairs: Tayo Akiwande, MIT; Jeff Welser, IBM

9:00 AM, IV.-1 Invited

Microelectronic Arrays and Electric Field Assisted Self-assembly of Component Structures for Micro/Nanofabrication Applications: *Michael J. Heller*¹; ¹Nanogen, 10398 Pacific Center Court, San Diego, CA 92121 USA

9:30 AM, IV.-2 Invited

Organic Electronics and E-Paper: *Pierre Wiltzius*¹; ¹Bell Laboratories/Lucent Technologies, 700 Mountain Ave., Murray Hill, NJ 07974 USA

10:00 AM, IV.-3 Invited

The First Solid State Qubit: *J. S. Tsai*¹; Y. Nakamura¹; Yu Pashkin¹;
¹Fundamental Research Laboratory, 34 Miyukigaoka, Tsukuba 305-8501 Japan

10:30 AM Break

10:50 AM, IV.-4 Invited

Issues, Concepts, and Challenges in Spintronics: *Sankar Das Sarma*¹; J. Fabian¹; X. D. Hu¹; I. Zutic¹; ¹University of Maryland, Dept. of Phys., College Park, MD 20742 USA

11:20 AM, IV.-5 Invited

Nanomechanical Systems: Progress, Challenges, and Ultimate Limits: *Michael Roukes*¹; ¹California Institute of Technology, Pasadena, CA USA

Tuesday PM, June 20, 2000

Session V.A. (DUC Ballroom A/B)
Displays and MEMs

Session Organizers: Vivek Subramanian, Berkeley; Hagen Klauk, Penn State

2:00 PM, V.A.-1 Invited

Nanoblock ICs and Smart Cereal Boxes: *Roger Stewart*¹; ¹Alien Technology Corporation, 18410 Butterfield Blvd., Suite 150, Morgan Hill, CA 95037 USA

2:30 PM, V.A.-2

A New Self-Aligned Top-Gate Polysilicon TFT Architecture for Low Temperature Processing: *Ronald T. Fulks*¹; Jackson Ho¹;
¹Xerox Palo Alto Research Center, 3333 Coyote Hill Rd., Palo Alto, CA 94304 USA

2:50 PM, V.A.-3

What Can We Learn From Organic Single Crystal Devices?: *J. H. Schon*¹; Ch. Kloc¹; B. Batlogg¹; ¹Lucent Technologies, Rm. MH 1E-318, 600 Mountain Ave., Murray Hill, NJ 07974-0636 USA

3:10 PM, V.A.-4

An Organic Thin Film Transistor Backplane for Flexible Liquid Crystal Displays: *C. D. Sheraw*¹; J. A. Nichols¹; D. J. Gundlach¹; J. R. Huang¹; C. C. Kuo¹; H. Klauk¹; T. N. Jackson¹; M. Kane²; J. Camp²; F. Cuomo²; B. Green²; ¹The Pennsylvania State University, Ctr. for Thin Film Devices and Elect. Mats. and Proc. Res. Lab., University Park, PA 16802 USA; ²Sarnoff Corporation, Princeton, NJ 08543 USA

3:30 PM Break

3:50 PM, V.A.-5

Development of A Novel Micromachined Magnetostatic Membrane Actuator: *Melvin Khoo*¹; Chang Liu¹; ¹University of Illinois at Urbana-Champaign, Microelec Lab, Urbana, IL 61801 USA

4:10 PM, V.A.-6

Development of A Novel Micro Electromechanical Tunable Capacitor with a High Tuning Range: *Jun Zou*¹; *C. Liu*¹; ¹University of Illinois at Urbana-Champaign, Microelec. Lab., Urbana, IL 61801 USA

Tuesday PM, June 20, 2000

Session V.B. (DUC Ballroom C/D)
Optical Sources

Session Organizer: Kevin Lear, Colorado State

2:00 PM, V.B.-1

Cylindrical Microcavity Light Emitters Realized with Double Oxide Confinement or Single-Defect Photonic Bandgap Crystals: *W. D. Zhou*¹; *J. Sabarinathan*¹; *B. Kochman*¹; *E. Berg*¹; *O. Qasaimeh*¹; *T. Brock*¹; *S. Pang*¹; *P. Bhattacharya*¹; ¹University of Michigan, Dept. of Elect. Eng. and Comp. Sci., Ann Arbor, MI 48109 USA

2:20 PM, V.B.-2

Room Temperature Continuous-Wave Operation of GaInNAs Long Wavelength VCSELs: *M. C. Larson*¹; *C. W. Coldren*^{1,2}; *S. G. Spruytte*²; *H. E. Petersen*¹; *J. S. Harris*²; ¹Lawrence Livermore National Laboratory, P.O. Box 808, L-222, Livermore, CA 94551 USA; ²Stanford University, CA USA

2:40 PM, V.B.-3

High Temperature Operation of GaInAsN Laserdiodes in the 1.3 μ m Regime: *M. Fischer*¹; *M. Reinhardt*¹; *A. Forchel*¹; ¹University of Wurzburg, Technische Physik, Am Hubland, 97074 Wurzburg, Germany

3:00 PM, V.B.-4

Low Threshold 1.3 μ m GaAsSb Lasers on GaAs Substrates: *O. Blum*¹; *J. F. Klem*¹; ¹Sandia National Laboratories, MS 0603, Albuquerque, NM 87185 USA

3:20 PM Break

3:40 PM, V.B.-5

Quaternary AlInGaN Based Vertically Conducted Light Emitting Diodes on SiC: *M. Asif Khan*¹; *V. Adivarahan*¹; *M. Shatalov*¹; *A. Lunev*¹; *J. W. Yang*¹; *G. Simin*¹; *R. Gaska*²; *M. Shur*²; ¹University of South Carolina, Dept. of ECE, Columbia, SC 29208 USA; ²Sensor Electronic Technology, Inc., Latham, NY 12110 USA

Tuesday PM, June 20, 2000, 8:15 PM - 10:00 PM

Rump Session

R.-1

High-K, Low-K or No \$K?:

Organizers: Jack Hergenrother, Lucent; Vivek Subramanian, UC Berkeley

R.-2

GaN vs. SiC: Is there an Argument Anymore?:

Organizer: Anant Agarwal, Cree, Inc., 4600 Silicon Dr., Durham, NC 27703 USA

R.-3

Long Wavelength Lasers on Short Wavelength Substrates:

Organizers: Olav Solgard, Stanford; Kevin Lear, Colorado State, CA USA

Tuesday PM, June 20, 2000, 9:00 PM - 11:00 PM

**Session III. (DUC Gallery)
Poster Session - Viewing Only**

III.-1

New Device Models of Quantum Well Infrared Photodetectors: Janet L. Pan¹; ¹Yale University, Becton Center, Rm. 505, 15 Prospect St., New Haven, CT 06520-8284 USA

III.-2

SiGe Low Loss Waveguides for 1.3 um Grown by Selective Epitaxy: A. Vonsovici¹; L. Vescan¹; S. P. Pogossian¹; ¹University of Surrey, Guildford GU2 XH UK

III.-3

Ferromagnetic Fe/Ag-GaAs Waveguide Structures for Wide-band Microwave Integrated Notch Filter Devices: Wei Wu¹; C. S. Tsai¹; C. C. Lee¹; H. J. Yoo¹; H. Hopster¹; D. L. Mills¹; ¹University of California, Dept. of Elect. and Comp. Eng. and Instit. of Surf. and Interf. Sci., Irvine, CA 92697 USA

III.-4

Memory Devices Utilizing Resonant Tunneling in Nanocrystalline Silicon Superlattices: L. Tsybeskov¹; L. Montes¹; G. Gron¹; R. Krishnan¹; P. Fauchet¹; B. White²; ¹University of Rochester, Dept. of Electr. & Comp. Eng., Computer Studies Bldg. 511, 160 Trustee Rd., Rochester, NY 14627-0231 USA; ²Motorola, SPS, Austin, TX USA

III.-5

Vacuum Microelectronic Electron Emitter by InP Double Barrier Diode Toward RF Application: Y. Miyamoto¹; M. Kurita¹; K.

Furuya¹; ¹Tokyo Institute of Technology, Dept. of Elect. & Electronic Eng., 2-12-1, O-okayama, Meguro, Tokyo 152-8552 Japan

III.-6

SB-Heterostructure Millimeter-Wave Zero-Bias Diodes: J. N. Schulman¹; D. H. Chow¹; C. W. Pobanz¹; H. L. Dunlap¹; C. D. Haeussler¹; ¹HRL Laboratories, LLC, 3011 Malibu Canyon Rd., Malibu, CA 90265 USA

III.-7

Five-Terminal Amorphous Silicon Thin-Film Transistor Structure: Sandrine Martin¹; Y. Feillens¹; J. Kanicki¹; ¹University of Michigan, Dept. of Elect. Eng. and Comp. Sci., 216 Engineering Programs, Bldg. 2609 Draper, Ann Arbor, MI 48109-2101 USA

III.-8

Lifetime Control By Low Energy Electron Irradiation and Hydrogen Annealing: J. Joe¹; J. Park¹; H. J. Kim¹; S. H. Lee¹; Z. Y. Shen¹; Y. Nishihara¹; ¹Ajou University, Dept. of Elect. Eng., Suwon 442-749 Korea

III.-9

Modeling High K Gate Current from p-type Si Inversion Layers: Y. Y. Fan¹; S. Mudanai¹; W. Qi¹; J. C. Lee¹; A. F. Tasch¹; L. F. Register¹; S. K. Banerjee¹; ¹The University of Texas at Austin; Microelect. Res. Ctr., 2.608A, R9950, Austin, TX 78758 USA

III.-10

Scaling Limit of Silicon Nitride Gate Dielectric for Future CMOS Technologies: Y. C. Yeol¹; Q. Lu¹; W. Lee¹; T. King¹; C. Hu¹; ¹University of California, Dept. of Elect. Eng. and Comp. Sci., Berkeley, CA 94720 USA

III.-11

60nm Planarized Ultra-thin Body Solid Phase Epitaxy MOSFETs: Peiqui Xuan¹; J. Kedzierski¹; V. Subramanian¹; J. Bokor¹; T. King¹; C. Hu¹; ¹University of California, Dept. of Elect. Eng. and Comp. Sciences, Berkeley, CA 94720 USA

III.-12

Design Optimization of Stacked Gate Oxides with Easy Evaluation of Gate Leakage in Deep Submicron MOSFET: Jinlong Zhang¹; Jiann S. Yuan¹; Yi Ma¹; Anthony S. Oates¹; ¹University of Central Florida, Sch. of Elect. Eng. and Comp. Sci., Orlando, FL 32816 USA

III.-13

A Novel Sub-10nm Transistor: Pranav Kalavade¹; K. C. Saraswat¹; ¹Stanford University, 725 Reseda Dr., 32 Sunnyvale, CA 94087 USA

III.-14

Reliability and Modeling of GaN-Based Light Emitting Diode: Hyunsoo Kim¹; Ji-Myon Lee¹; B. Huh¹; Sang-Woo Kim¹; Dong-Joon Kim¹; Seong-Ju Park¹; Hyunsang Hwang¹; ¹Kwangju Institute of Science and Technology, Dept. of Mats. Sci. and Eng., #1, Oryong-dong, Puk-gu, Kwangju 500-712 Korea

III.-15

pH Sensors Based on Wide Bandgap Semiconductors: A. Denisenko¹; A. Aleksov¹; I. Daumiller¹; E. Kohn¹; ¹University of Ulm,

Dept. of Elect. Devs. & Cir., Albert-Einstein-Allee 45, 89081 Ulm, Germany

III.-16

Very Short Channel Metal-Gate Schottky Source/Drain SOI-PMOSFETs and their Short Channel Effect: A. Itoh¹; M. Saitoh¹; M. Asada¹; ¹Tokyo Institute of Technology, Fac. of Eng., Dept. of Elect. and Elect. Eng., 2-12-1 O-okayama, Meguro-ku, Tokyo 152 8552 Japan

III.-17

Electron Transport in a Single Silicon Quantum Dot Structure using A Vertical Silicon Probe: Katsuhiko Nishiguchi¹; Shunri Oda¹; ¹Tokyo Institute of Technology, Res. Ctr. for Quantum Effect Electr., O-okayama, Meguro-Ku, Tokyo 152-8552 Japan

III.-18

A Silicon MOSFET/Field Emitter Array Fabricated using CMP: C. Y. Hong¹; A. I. Akinwande¹; ¹Massachusetts Institute of Technology, Microsystems Technology Laboratories, 39-653, 60 Vassar St. Cambridge, MA 02139 USA

III.-19

0.13 um Gate-Length In_{0.52}A_{10.48}As/In_{0.53}Ga_{0.47}As Metamorphic HEMTs on GaAs Substrate: D. C. Dumka¹; G. Cueva¹; W. E. Hoke²; P. J. Lemonias²; I. Adesida¹; ¹University of Illinois, Dept. of Elect. and Comp. Eng. and Microelec. Lab., 208 N. Wright St., Urbana-Champaign, IL 61801 USA; ²Raytheon RF Components, MA USA

III.-20

HBT on LEO GaN: L. McCarthy¹; Y. Smorchkova¹; P. Fini¹; H. Xing¹; M. Rodwell¹; J. Speck¹; S. DenBaars¹; U. Mishra¹; ¹University of California-Santa Barbara, ECE Dept., Santa Barbara, CA 93106 USA

Wednesday AM, June 21, 2000

Joint Plenary Session with EMC (*Sturm Auditorium*)
8:30 AM - 10:00 AM

DRC/EMC PLENARY LECTURE/STUDENT AWARDS

Ceremony: 8:20 AM

Room: Sturm Auditorium

Session Chairman: M. R. Melloch, Purdue University, School of Electrical and Computer Engineering, West Lafayette, IN 47907 USA

Plenary Speaker: L. L. Kazmerski

Topic: Photovoltaics Research and Development:: A Tour Through the 21st Century: *L. L. Kazmerski*¹; ¹National Renewable Energy Laboratory, 1617 Cole Blvd, MS 3221, Golden, CO 80401 USA

BREAK: 9:20 AM - 10:00 AM

Wednesday AM, June 21, 2000

Session VI.A. (Sturm Auditorium)
SiC Power Switching Devices

Session Organizer: Anant Agarwal, Cree, Inc., 4600 Silicon Dr., Durham, NC 27703 USA

10:00 AM, VI.A.-1

2.7 kV Epitaxial Lateral Power DMOSFETs in 4H-SiC: *J. Spitz*¹; M. R. Melloch¹; J. A. Cooper, Jr.¹; G. Melnychuk²; S. E. Saddow¹; ¹Purdue University, School of Elect. and Comp. Eng., West Lafayette, IN 47907-1285 USA; ²Mississippi State University, MS USA

10:20 AM, VI.A.-2

Improved Implanted RESURF MOSFETs in 4H-SiC: *Sujit Banerjee*¹; K. Chatty¹; T. P. Chow¹; R. J. Gutmann¹; ¹Rensselaer Polytechnic Institute, Center for Integrated Elect. and Elect. Manuf., CII-6015110 8th St., Troy, NY 12180-3590 USA

10:40 AM, VI.A.-3

An Implanted Emitter 4H-SiC Bipolar Transistor with High Current Gain: *Yi Tang*¹; J. B. Fedison¹; T. Chow¹; ¹Rensselaer Polytechnic Institute, Center for Intergrated Electr. and Electr. Manuf., CII-6015, 110 8th St., Troy, NY 12180-3590 USA

11:00 AM, VI.A.-4

1800V, 3.8 Bipolar Junction Transistors in 4H-SiC: *Sei-Hyung Ryu*¹; Anant K. Agarwal¹; Ranbir Singh¹; John W. Palmour¹; ¹Cree, Inc. 4600 Silicon Dr., Durham, NC 27703 USA

11:20 AM Break

11:40 AM, VI.A.-5

Switching Characteristics of 3kV 4H-SiC GTO Thyristors: *Jeffrey B. Fedison*¹; T. Chow¹; A. Agarwal²; S. Ryu²; R. Singh²; O. Kordin²; J. Palmour²; ¹Rensselaer Polytechnic Institute, Ctr. for Integrated Electr. and Electr. Manuf., CII-6015, 110 8th St., Troy, NY 12180-3590 USA; ²Cree, Inc.

Wednesday AM, June 21, 2000

Session VI.B. (DUC Ballroom A/B)
III-V FETs and HBTs

Session Organizer: Yasuyuki Miyamoto, Tokyo Institute of Technology

10:00 AM, VI.B.-1 Invited

Highly Efficient High Power InP HEMT Amplifiers for High Frequency Applications: *Y. C. Chen*¹; R. Lai¹; D. L. Ingram¹; T. Block¹; M. Wojtowicz¹; P. H. Liu¹; H. C. Yen¹; A. Oki¹; D. C. Streit¹; K.

Yano¹; ¹TRW Electronics & Technology Division, One Space Park, Redondo Beach, CA 90278 USA

10:30 AM, VI.B.-2

High Ft and Fmax InAlAs/InGaAs Transferred-Substrate HBTs: *Y. Betser*¹; D. Mensa¹; S. Jaganathan¹; T. Mathew¹; M. J.W. Rodwell¹; ¹University of California-Santa Barbara, ECE Dept., Santa Barbara, CA 93106 USA

10:50 AM, VI.B.-3

MOCVD-Grown 175 GHz InP/GaAs_xSb_{1-x}/InP DHBTs with High Current Gains Using Strained and Heavily C-Doped Base Layers: *M. W. Dvorak*¹; N. Matine¹; S. P. Watkins¹; C. R. Bolognesi¹; ¹Simon Fraser University, Schl. of Eng. Sci., and Dept. of Phys., 8888 University Dr., Burnaby, BC, Canada V5A 1S6

11:10 AM, VI.B.-4

Design and Characterization of GaAs/Ga_{0.89}In_{0.11}N_{0.02}As_{0.98}/GaAs NpN Double Heterojunction Bipolar Transistors with Low Turn On Voltage: *R. J. Welty*¹; H. P. Xin¹; K. Mochizuki¹; C. W. Tu¹; P. M. Asbeck¹; ¹University of California at San Diego, LaJolla, CA 92093-0407 USA

11:30 AM Break

11:50 AM VI.B.-5

First Demonstration of the AlGaAs/InGaAsN/GaAs P-n-P Double Heterojunction Bipolar Transistor: *P. C. Chang*¹; N. Y. Li²; J. R. Larouche³; C. Monier⁴; A. G. Baca¹; H. Q. Hou²; E. Ren³; S. J. Pearton⁴; ¹Sandia National Laboratories, Advanced Semiconductor Technology, P.O. Box 5800, M.S. 0603, Albuquerque, NM USA; ²EMCORE; ³University of Florida, Chem. E.; ⁴University of Florida, MSE

Wednesday PM, June 21, 2000

Session VII.A. (*Sturm Auditorium*)
Quantum Devices

Session Organizer: Richard Kiehl, University of Minnesota

2:00 PM, VII.A.-1

Single Electron Memory Utilizing Nano-Crystalline Si over Short Channel Silicon-on-Insulator Transistors: *B. J. Hinds*¹; A. Dutta¹; B. F. Yun¹; C. T. Yamanaka¹; D. S. Hatanani¹; S. Oda¹; ¹Tokyo Institute of Technology, Res. Ctr. for Quantum Effect Elect, 2-12-1 O-okayama, Megura-ku, Tokyo 152-8552 Japan

2:20 PM, VII.A.-2

Multiple-Valued Memory Operation in SiN-Based Single-Electron Memory: *G. Sunamura*¹; H. H. Kawaura¹; I. T. Sakamoto¹; J. T. Bab¹; ¹NEC Fundamental Research Laboratories, 34 Miyukigaoka, Tsukuba-shi, Ibaraki 305-8501 Japan

2:40 PM, VII.A.-3

GaAs Single Electron Transistors and Logic Inverters Based on Schottky Wrap Gate Structures: *S. Kasai*¹; H. Hasegawa¹; ¹Hokkaido University, Res. Ctr. for Interface Quant. Electr. and Grad. Sch. of Electr. and Info. Eng., North 13, West 8, Sapporo 060-8628 Japan

3:00 PM, VII.A.-4

Experimental Studies of Clocked Quantum-dot Cellular Automata Devices: *Alexei Orlov*¹; A. Togh¹; I. Amlani¹; R. Kumamuru¹; R. Ramasubramaniam¹; C. Lent¹; G. Bernstein¹; G. Snider¹; ¹University of Notre Dame, Dept. of Elect. Eng., Notre Dame, IN 46556 USA

3:20 PM Break

3:40 PM, VII.A.-5

Development of Delta-B/I-Si/Delta-Sb and Delta-B/I-Si/Delta-Sb/I-Si/Delta-B Resonant Interband Tunnel Diodes for Integrated Circuit Application: *Sean L. Rommel*¹; N. Jin¹; T. E. Dillon¹; S. J. diGiacomo¹; J. Banyai¹; B. M. Cord¹; C. D'Imperio¹; D. J. Hancock¹; N. Kirpalani¹; V. Emanuele¹; P. R. Berger¹; P. E. Thompson²; K. D. Hobart²; R. Lake³; ¹University of Delaware, Dept. of Elect. & Comp. Eng., 140 Evans Hall, Newark, DE 19716 USA; ²NRL, Washington, DC USA; ³Raytheon Systems, Dallas, TX USA

4:00 PM, VII.A.-6

Monolithic Integration of InAlAs/InGaAs/InP HEMTs and InAs/AISb/GaSb Resonant Interband Tunneling Diodes (RITDs) for High Speed Integrated Circuits: *P. Fay*¹; J. Lu¹; Y. Xu¹; G. H. Bernstein¹; D. H. Chow¹; J. N. Schulman¹; H. L. Dunlap¹; J. De Los Santos¹; ¹University of Notre Dame, Dept. of Elect. Eng., Notre Dame, IN 46556 USA

Wednesday PM, June 21, 2000

Session VII.B. (DUC Ballroom A/B)
Photodetectors and Phototransceivers

Session Organizer: Pallab Bhattacharya, University of Michigan

2:00 PM, VII.B.-1 Invited

Ultrafast Uni-Traveling-Carrier Photodiode: *Hiroshi Ito*¹; Tadao Ishibashi¹; ¹NTT Photonics Laboratories, 3-1, Morinosato Wakamiya, Atsugi-shi, Kanagawa 243-0198 Japan

2:30 PM, VII.B.-2

Ultraviolet Photon Counting with GaN Avalanche Photodiodes: *K. A. McIntosh*¹; S. Verghese¹; R. J. Molnar¹; L. J. Mahoney¹; K. M. Molvar¹; M. K. Connors¹; R. L. Aggarwal¹; I. L. Melngailis¹; ¹Massachusetts Institute of Technology; Lincoln Laboratory, 244 Wood St., Lexington, MA 02420-9108 USA

2:50 PM, VII.B.-3

Dark Current Reduction and Operational Wavelength Shift in Normal Incidence InAs/GaAs QDIPs through the Introduction of AlGaAs Layers in the Active Region of the Detector: *O. Baklenov*¹; Z. H. Chen¹; E. T. Kim¹; I. Mukhametzhanov¹; A. Madhukar¹; F. Ma²; Z. Ye²; B. Yang²; J. Campbell²; ¹University of Southern California, Mats. Svc. Dept., 3651 Watt Way VHE 506, Los Angeles, CA 90089 USA; ²University of Texas at Austin, Austin, TX USA

3:10 PM, VII.B.-4

P-I-N Photodiodes in Metamorphic InAlAs/InGaAs/GaAs for Long Wavelength Applications: *J.-H. Jang*¹; G. Cueva¹; D. C. Dumka¹; W. E. Hoke²; P. J. Lemonias²; I. Adesida¹; ¹University of Illinois, Dept. of Elect. and Comp. Eng. and Microelec. Lab., 208 N. Wright St., Urbana-Champaign, IL 61801 USA; ²Raytheon RF Products, MA USA

3:30 Break

3:50 PM, VII.B.-5

Monolithically Integrated Low-Power Phototransceiver Incorporating Microcavity LEDs and Multiquantum Well Phototransistors: *O. Qasimeh*¹; W. Zhou¹; P. Bhattacharya¹; D. Huffaker²; D. Deppe²; ¹University of Michigan, Dept. of Elect. Eng. and Comp. Sci., Ann Arbor, MI 48105-2122 USA; ²University of Texas at Austin, Austin, TX USA